

# **GaAs Based High-Power Photodiodes for Advanced LIGO**

**LIGO-G020370-00-Z**

**David Jackrel, PhD Candidate**

**Dept. of Materials Science and Engineering**

**Advisor: James S. Harris**

**LSC Conference, LHO**

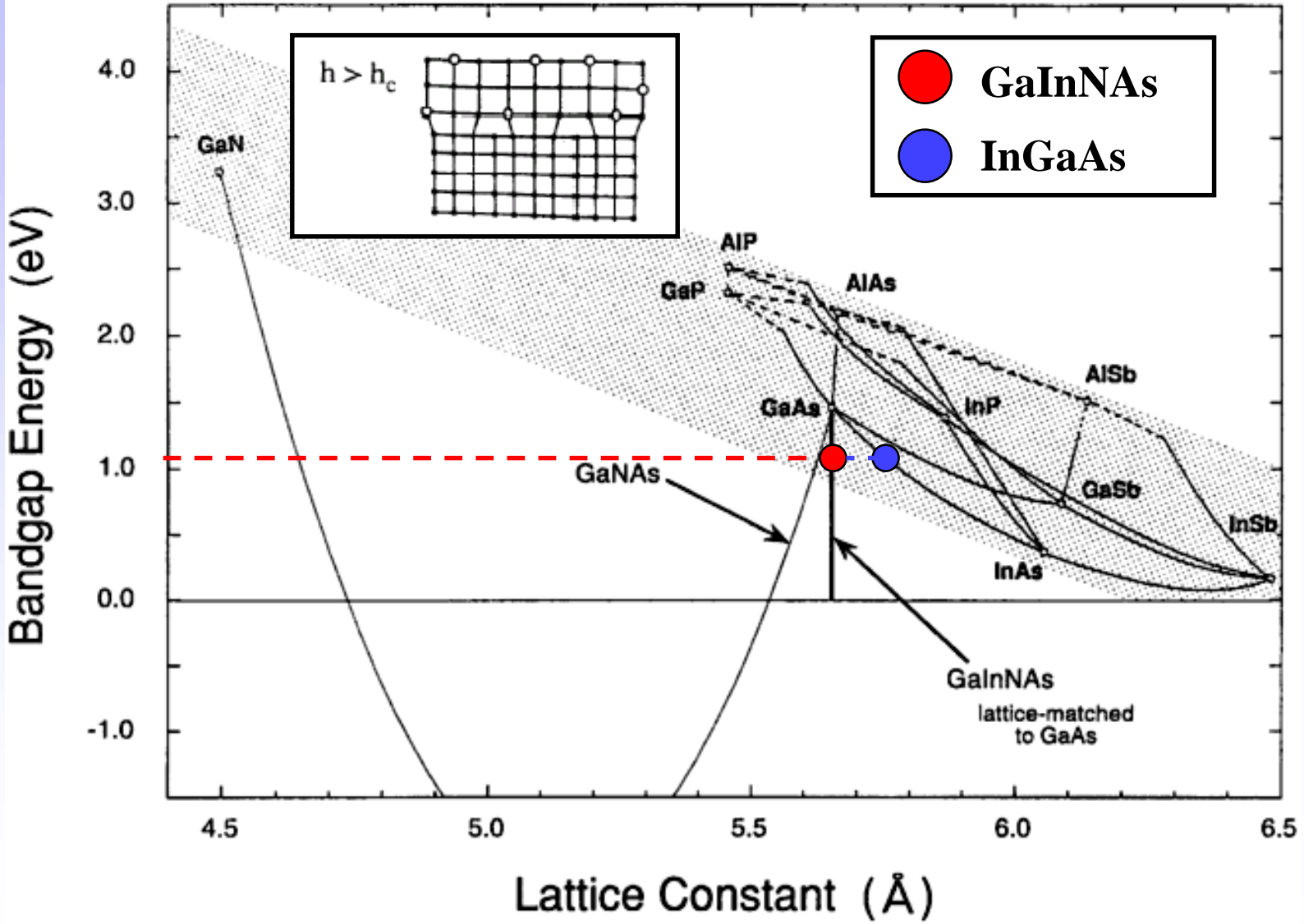
**August 19<sup>th</sup>-22<sup>nd</sup>, 2002**

# Photodiode Specifications

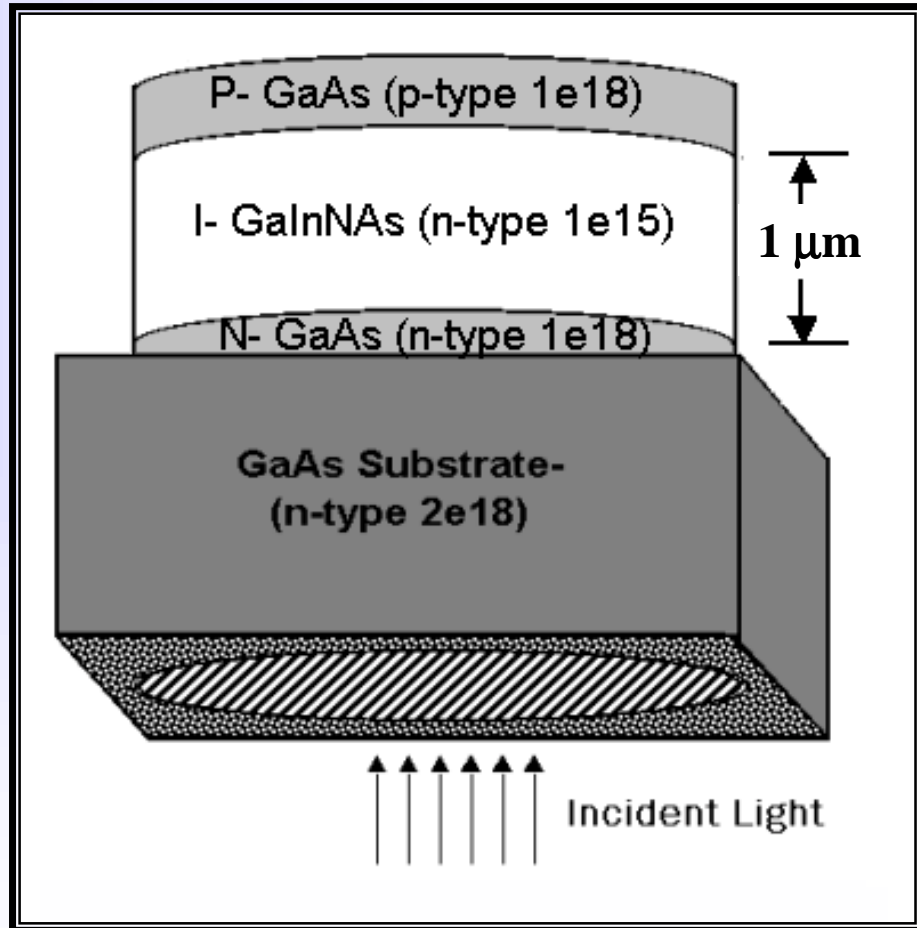
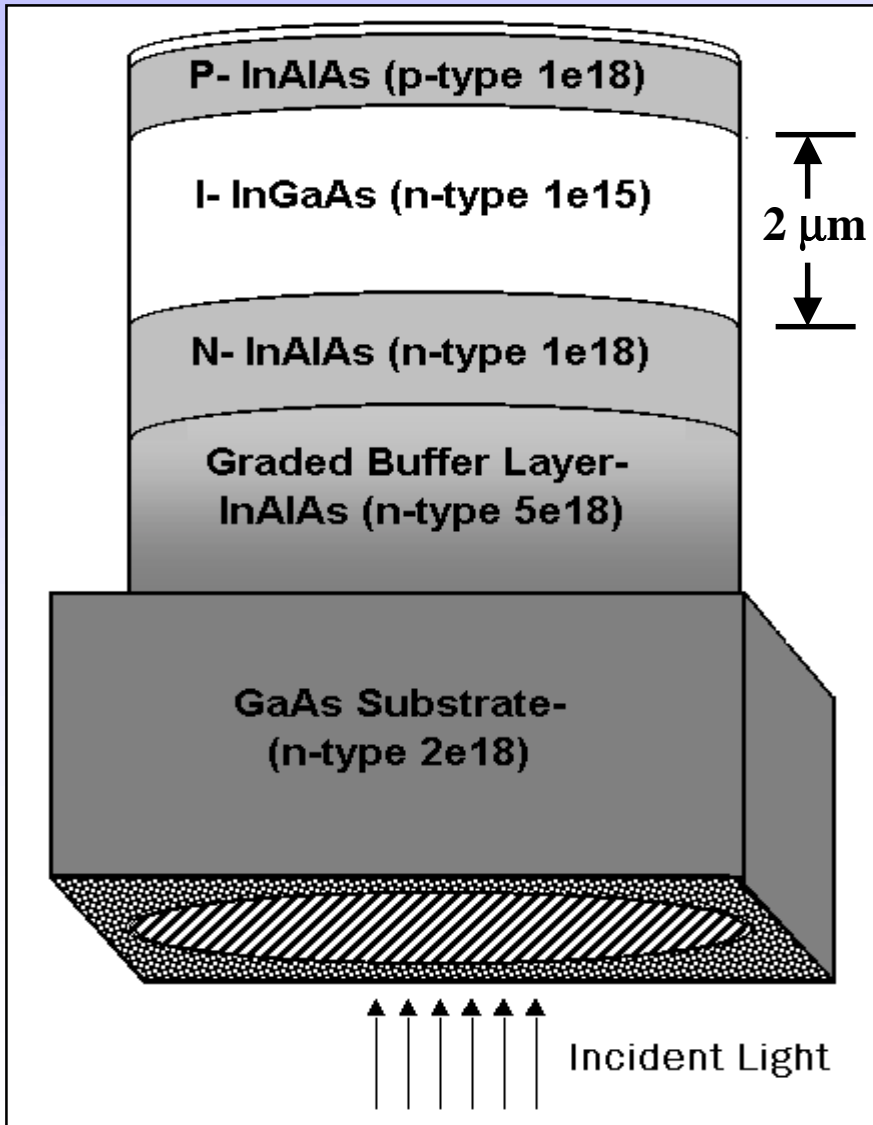


Parameter	LIGO I	Advanced LIGO
<b>Steady-State Power</b>	0.6 W	~1 W
<b>Modulation Frequency</b>	< 29 MHz	100 kHz ~ 180 MHz
<b>Quantum Efficiency</b>	> 80%	> 90%
<b>Laser Wavelength</b>	1064nm	1064nm
<b>Detector Design</b>	Bank of 6(+) PDs	1 PD

# InGaAs vs. GaInNAs

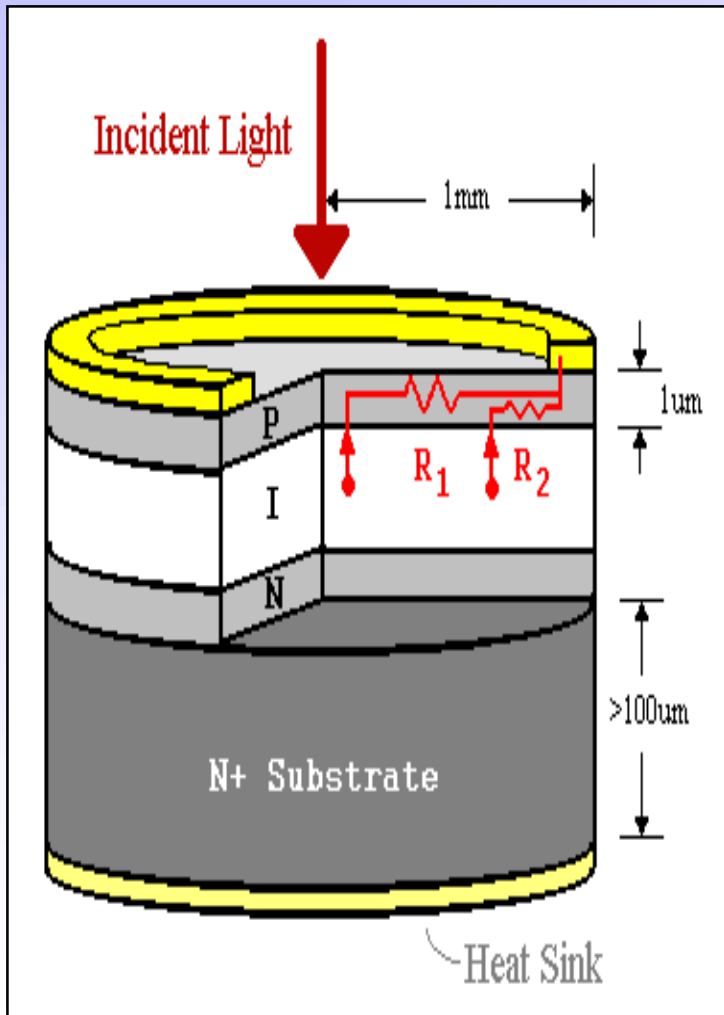


# InGaAs vs. GaInNAs PD Designs

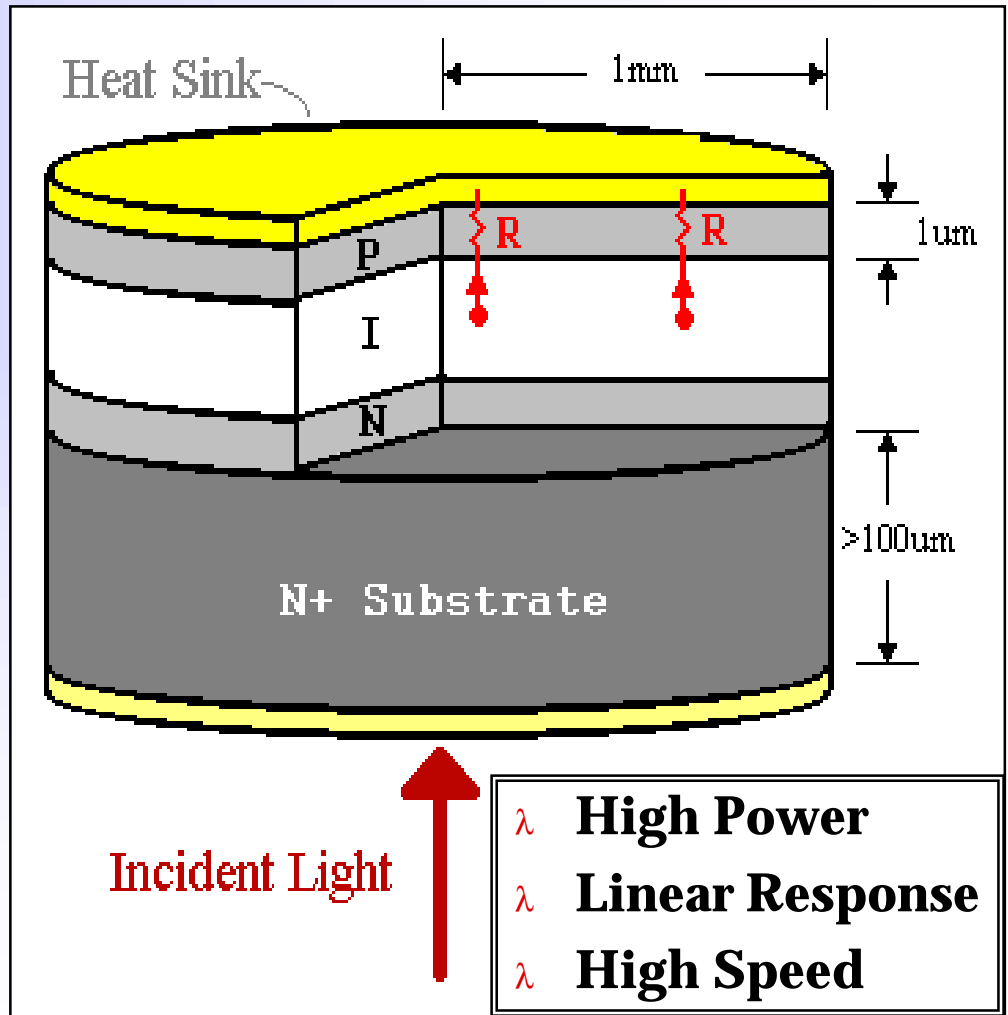


**GaInNAs lattice-matched  
to GaAs!**

# Rear-Illuminated PD Advantages

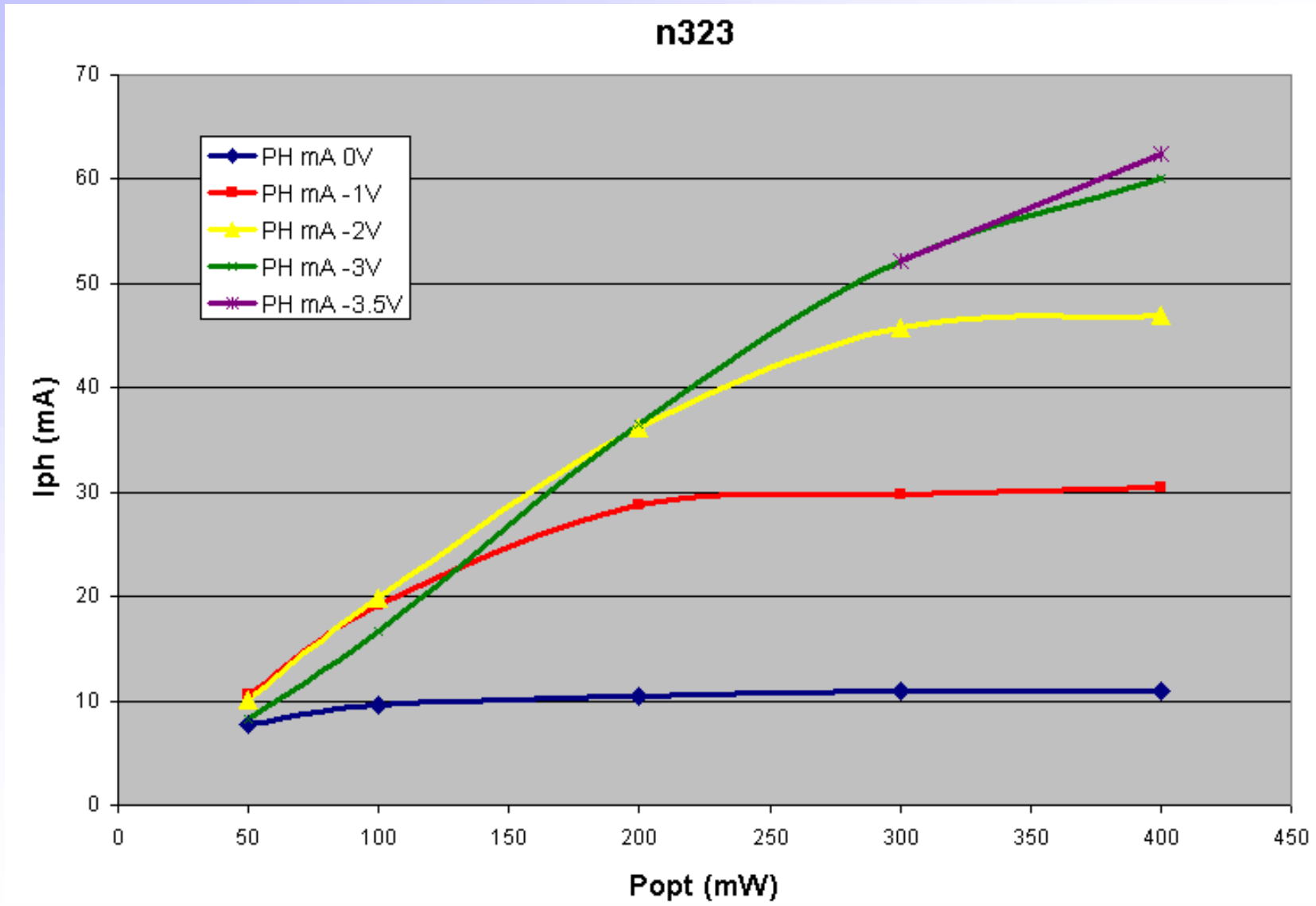


**Conventional PD**



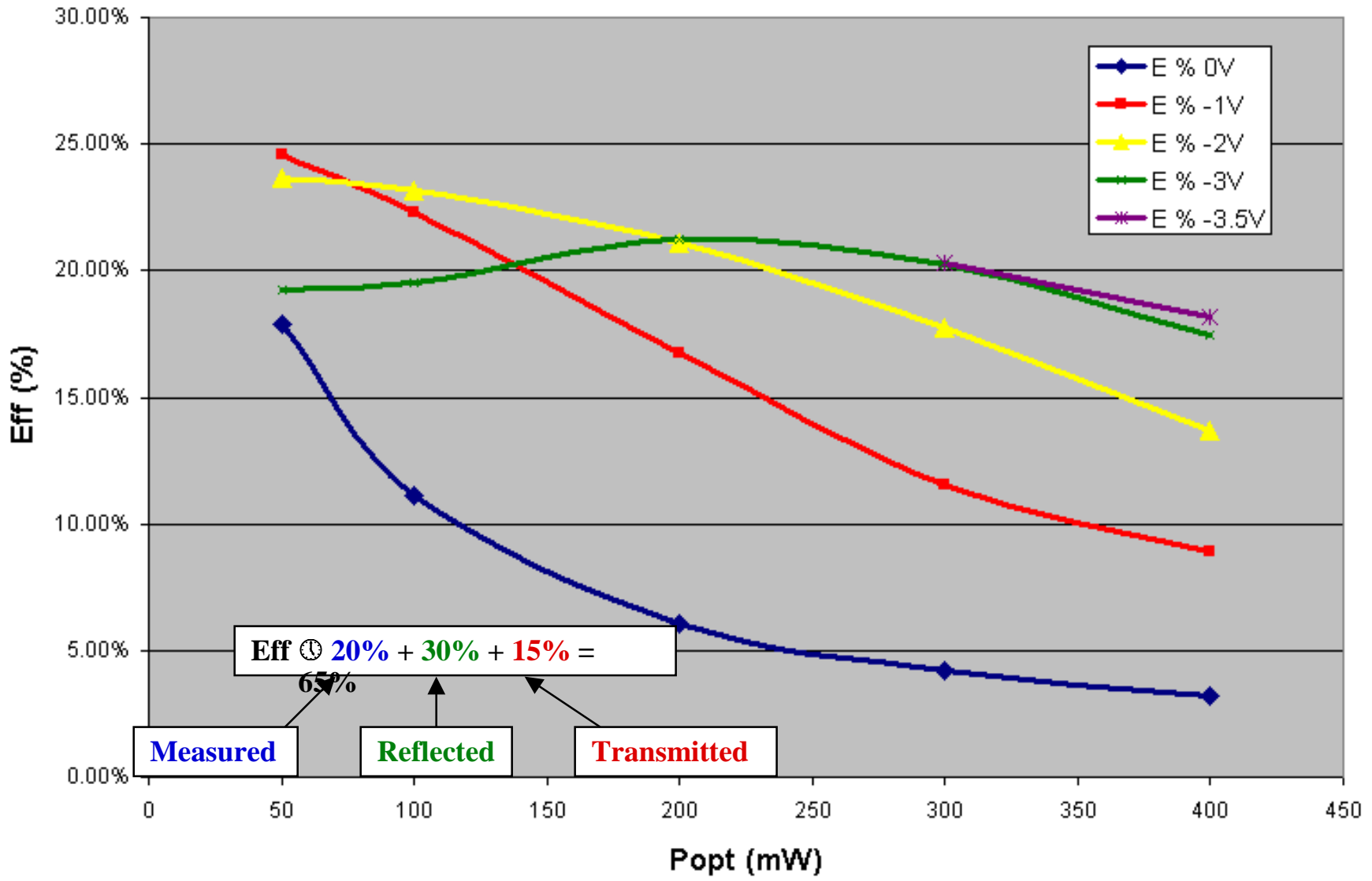
**Adv. LIGO Rear-Illuminated PD**

# GalNAs Photodiode Linearity

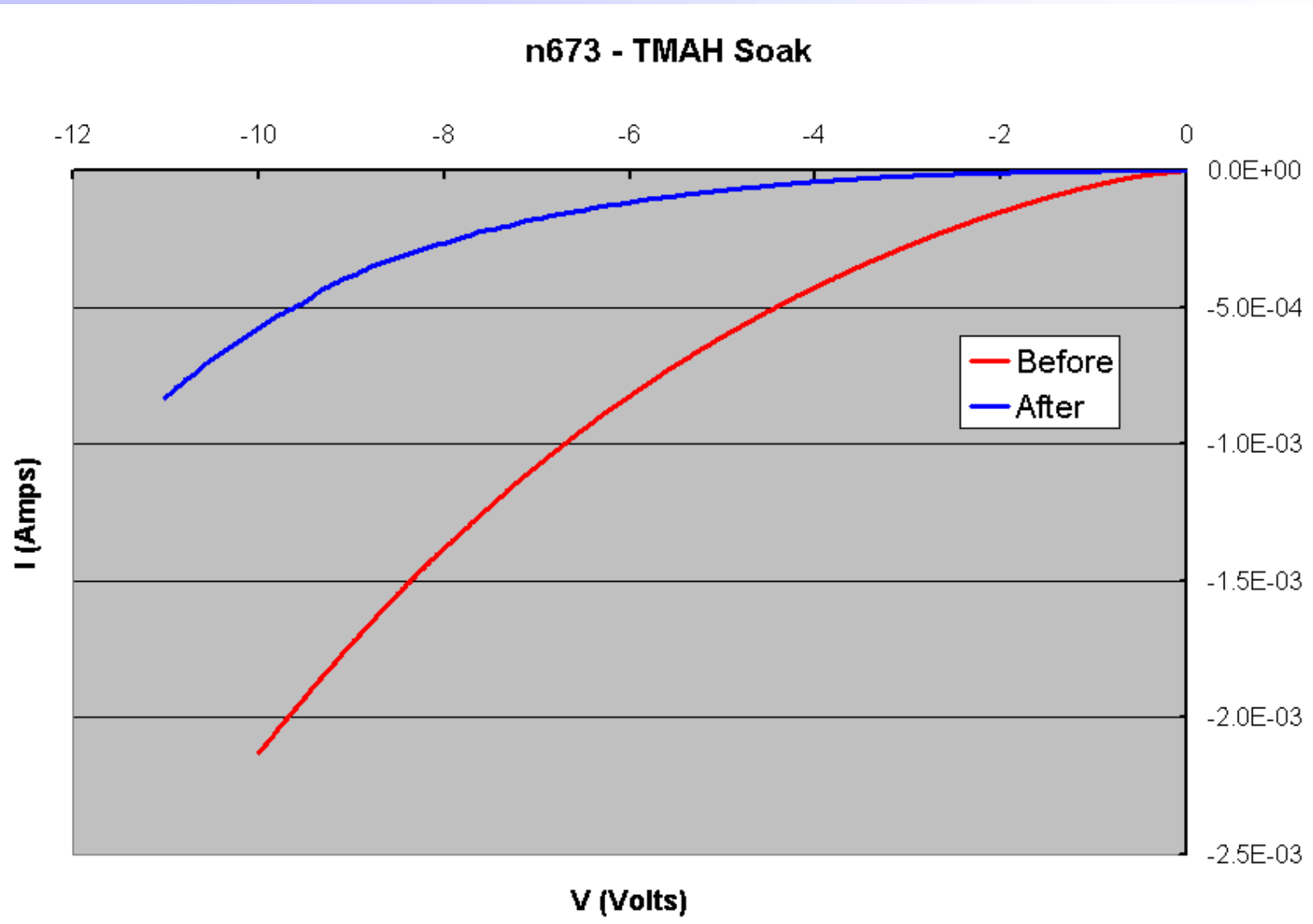


# GalNAs PD Efficiency

n323

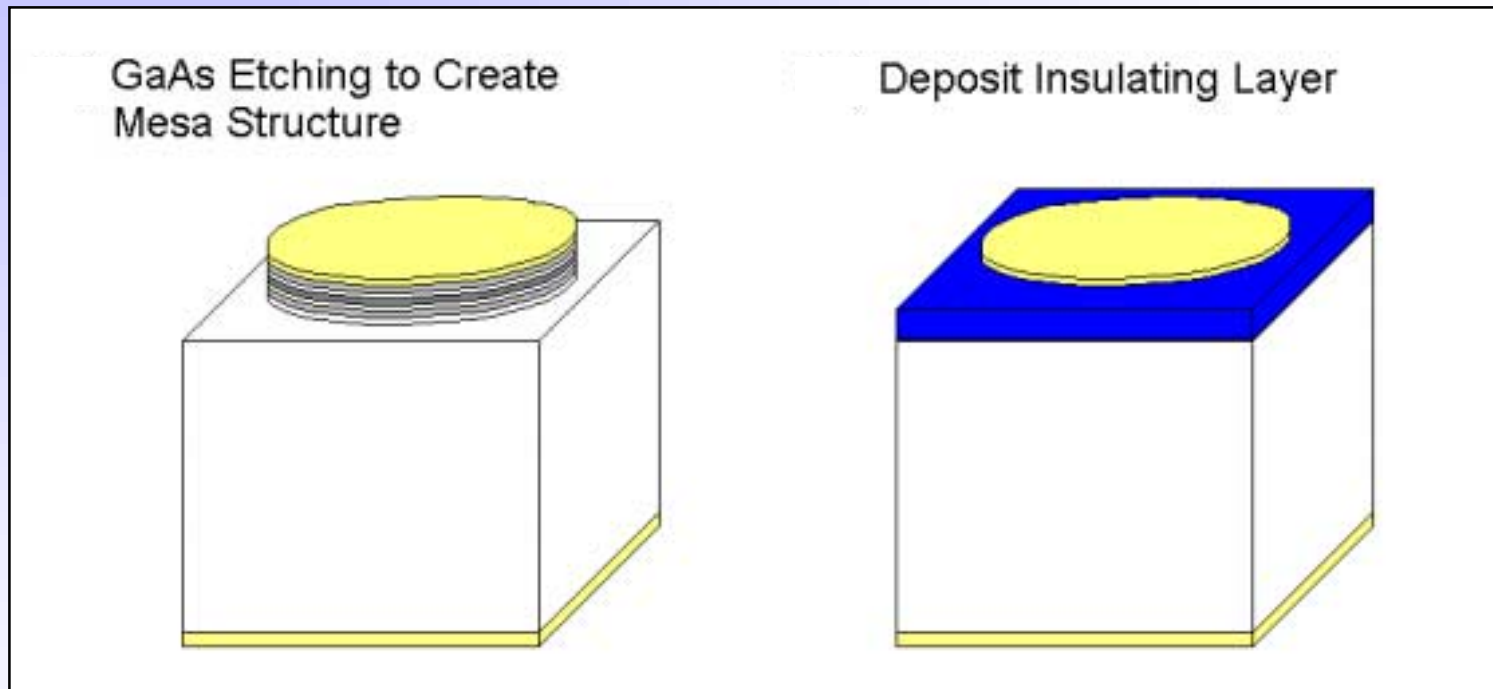


# InGaAs PD: Dark Current





# Junction “Passivation”



GaAs Etching to Create Mesa Structure

Deposit Insulating Layer

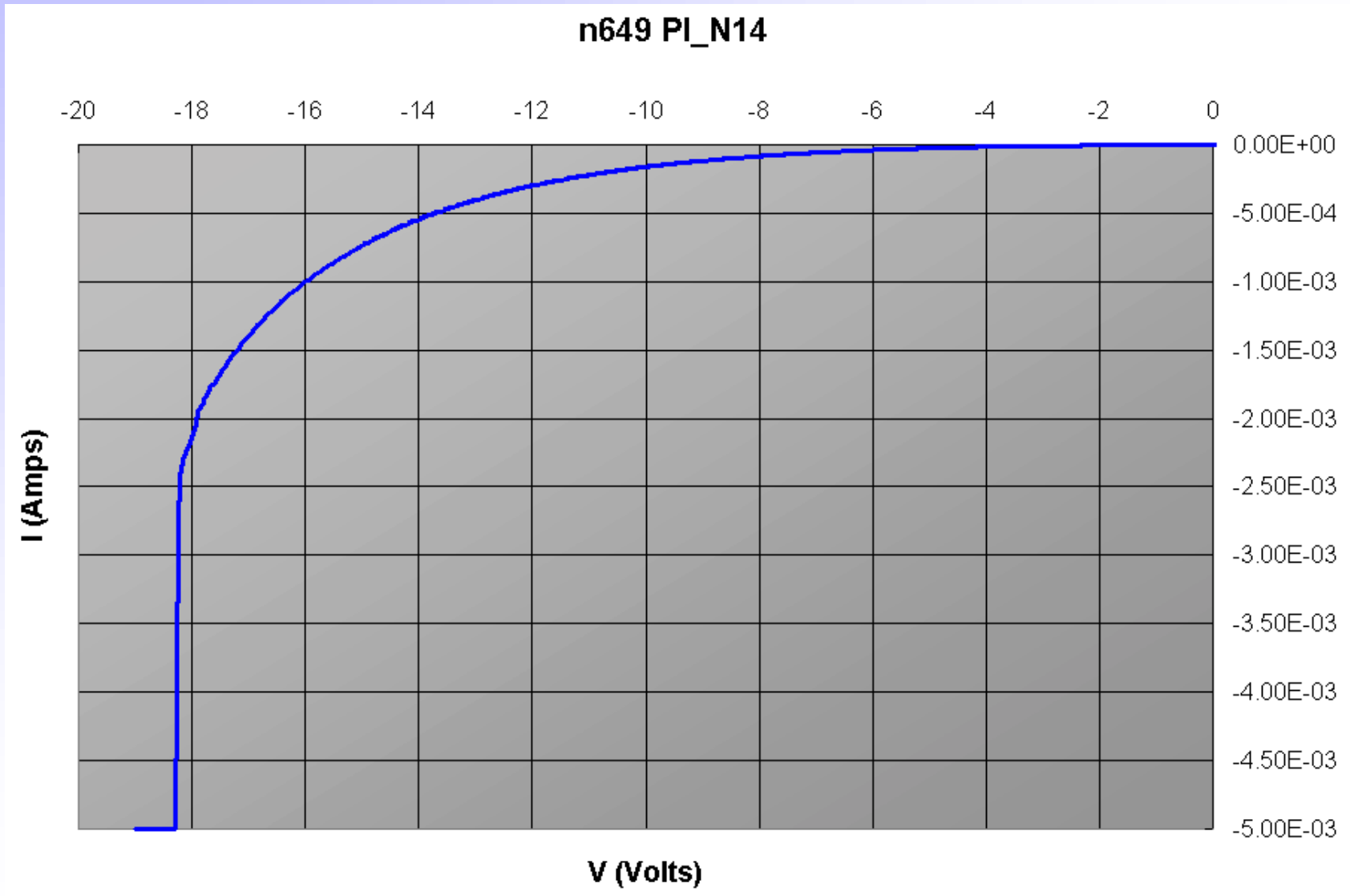
**Plasma Etching**

→ Ar, BCl<sub>3</sub>, Cl<sub>2</sub>

**Polyimide Spinning**

→ Cresol-novolak Resin  
(AZ 9260 PR)

# InGaAs: Polyimide "Passivated"



## $\lambda$ GaInNAs

- $\lambda$  2-micron I-Layer
- $\lambda$  Etching and Passivating

## $\lambda$ InGaAs

- $\lambda$  Thinned Substrate
- $\lambda$  Etching and Passivating

## $\lambda$ RF Setup

- $\lambda$  High Power Voltage Source